



843.41042X00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): K. Hayano, et al.

Application No.: 10/025,457

Filing Date: December 26, 2001

Allowed: May 18, 2004

Fee Paid: August 18, 2004

For: METHOD OF MANUFACTURING PHOTOMASK AND METHOD OF
MANUFACTURING SEMICONDUCTOR INTEGRATED CIRCUIT
DEVICE

Art Unit: 1756

Examiner: S. Mohamedulla

**RESPONSE TO NOTICE OF DRAWING INCONSISTENCY
WITH SPECIFICATION**

Mail Stop Issue Fee
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

October 8, 2004

Sir:

In response to the Notice Of Drawing Inconsistency With Specification mailed
September 8, 2004, please amend the above-identified application as listed in the
following, and as set forth on the following pages:

Amendments to the Specification; and

Remarks are included following the amendments.